



NOTES:

1. MATERIAL: UVFS
2. COATING (S1) : ENHANCED AG COATING
 $R_s > 99\% @ 750\text{ nm} - 1000\text{ nm}$, $|GDD_s| < 20\text{ fs}^2$, $AOI = 45^\circ$
 $R_p > 98.5\% @ 750\text{ nm} - 1000\text{ nm}$, $|GDD_p| < 30\text{ fs}^2$, $AOI = 45^\circ$
3. CLEAR APERTURE (S1) : $> 80\%$ CA
4. SURFACE QUALITY (S1) : 40/20 (S/D)
5. SURFACE FLATNESS (S1) : $\lambda / 10 @ 633\text{ nm}$
6. PARALLELISM (S1, S2) : $< 3\text{ arcmin}$
7. CHAMFER: $< 0.2\text{ mm}, 45^\circ$
8. BACK SURFACE (S2) : FINE GROUND

DRAWING PROJECTION			LBTEK			
	NAME	DATE				
DRAWN	YZENG	Jul./25th/24	ENHANCED SILVER ULTRAFAST MIRROR $\phi 12.7\text{ mm} \times 6\text{ mm}, 750\text{ nm} - 1000\text{ nm}$			
APPROVAL	WCHENG	Jul./25th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	1.67 g	5:1	A